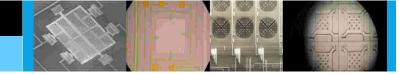
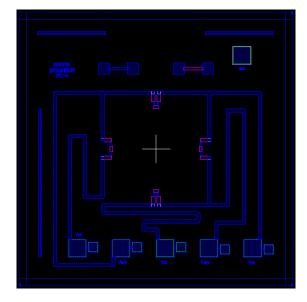
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MTPD-015A-04G-F

Uncompensated Pressure Sensor Die





The MTPD015 series piezo-resistive pressure sensor dies are manufactured on six inch silicon wafers in a class 100 clean room using a state of the art 1.2 micron CMOS facility and are then bulked micro-machined in a class 1000 clean room. The wafers are batch manufactured using a electrochemical etch stop process to achieve excellent repeatability.

Applied pressure deforms a diaphragm causing piezo-resistors to change their resistance. This change in four resistors, which constitute a Wheat Stone Bridge, results in a pressure-proportional voltage.

Dies are probed, inked, diced and visually inspected and shipped on tapes, in rings or in waffle packs. Dies can be mounted on ceramic or PCB substrates or packaged in application specific packages for measuring pressure in noncorrosive media.

FEATURES

- Piezo-resistive bridge
- Surface passivation
- Solid state
- High reliability
- Optimally sized for application
- Low cost design
- Meets industry specifications
- 6" wafer availability
- 100% factory tested
- Excellent repeatability
- Rated pressure of sensor 0 to 15 psi

THE MAIN FIELD OF APPLICATIONS

- ✓ Mobile altimeter/barometer
- ✓ Weather forecast
- ✓ Automotive
- Industrial electronics
- ✓ Consumer electronics

MEMSENZ[™] I Transduction Principle Capacitive Processing Technology Bulk/Deep RIE Actuation Mechanism Force (External) Signal Condition Two chips/Single chip MEMSENZ[™] II Transduction Principle Piczoresistive Processing Technology Bulk/Deep Wet Etch Actuation Mechanism Pressure (External) Signal Condition Two chips/Single chip MEMSENZ[™] III Transduction Principle Resistive Processing Technology Surface Actuation Mechanism Thermal Signal Condition Two chips MEMSENZ[™] IV Transduction Principle Capacitive Processing Technology Bulk Actuation Mechanism Sound Signal Condition Two chips

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MTPD-015A-04G-F

Uncompensated Pressure Sensor Die

TECHNICAL DATA

Maximum ratings

Specification	Min.	Тур.	Max.	Unit
Operating Temperature	-40	-	+ 85	°C
Storage Temperature	-40	-	+125	°C
Supply Voltage	-	5	10	V
Operating Current	-	0.7	-	mA

Data

Temperature=22±2 ℃, Relative humidity=45±5%, Supply voltage=5V

Specification	Min.	Тур.	Max.	Unit
		-	15	psiA
Operating Pressure Range	0.0	-	776	mmHg
	0	-	103	kpa
	0	-	1	bar
		-	75	psiA
Max. Pressure	0	-	3876	mmHg
	0	-	517	kpa
	0	-	5.2	bar
Zero Pressure Offset Voltage (before bonding)	-3	-	3	mV/V
<u> </u>	19	29	39	μV/V/mmHg
Sopoitivity	1.0	1.5	2.0	mV/V/psi
Sensitivity	0.1	0.2	0.3	mV/V/kpa
	72	111	145	mV/bar
Full Scale Span	75	115	150	mV
Non Linearity	-0.5	0	+0.5	%FS
Bridge Resistance (see note 5)	4500	5000	5500	Ω
TCO	-215	-65	85	μV/V/℃
TCR	1900	2300	2700	ppm/℃
TCS	-12	-18	-24	%FS/℃

- 1. Supply voltage DC and AC up to 5kHz, $V_{pp} = 10V \pm 0.1VDC$
- 2. Current is linear in full range
- 3. Total error at half span is based on the difference between half span measurement and a straight line projection over the span of the device where $O\left(\frac{S}{2}\right) \frac{O\left(0\right) + O\left(S\right)}{2} = 100$

NL(%) =
$$\frac{O(\frac{S}{2}) - \frac{O(0) + O(3)}{2}}{O(\frac{S}{2})} x 100$$

- 4. Top side pressure application
- 5. Resistance is measured by sourcing a constant current of 0.7mA
- 6. Parameters (except zero pressure offset which is measured directly) are computed from individual piezo-resistance measurements made at different pressures under application of a current of 0.7mA, which represents the typical operating conditions
- 7. TCO, TCR & TCS are tested from 0°C to 50°C

MEMSENZTM I Transduction Principle Capacitive Processing Technology Bulk/Deep RIE Actuation Mechanism Force (External) Signal Condition Two chips/Single chip MEMSENZ[™] II Transduction Principle Piezoresistive Processing Technology Bulk/Deep Wet Etch Actuation Mechanism Pressure (External) Signal Condition Two chips/Single chip

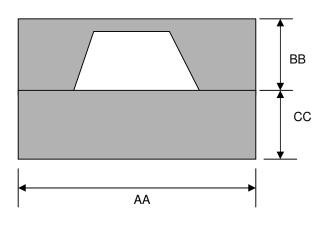
MEMSENZ[™] III Transduction Principle Resistive Processing Technology Surface Actuation Mechanism Thermal Signal Condition Two chips

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MTPD-015A-04G-F

Uncompensated Pressure Sensor Die

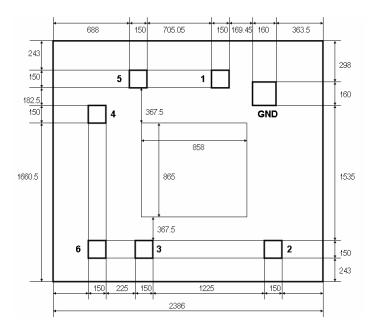
DIMENSIONS



Dim.	Typical	Tolerance	Units
AA	2386	± 0.33	μm
BB	403	± 10	μm
CC	700	± 25	μm
Dicing process	100	± 15	μm

Note: Dimension AA is prior to dicing process.

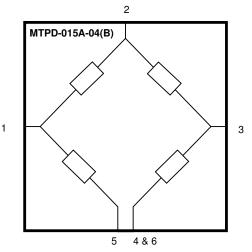
ELECTRICAL AND DIE LAYOUT



Note

- All dimensions are in µm.
- Mask fabrication tolerance of ±0.3um
- Design fabrication tolerance of ±0.03um

MEMSENZ[™] I Transduction Principle Capacitive Processing Technology Bulk/Deep RIE Actuation Mechanism Force (External) Signal Condition Two chips/Single chip MEMSENZ[™] II Transduction Principle Piezoresistive Processing Technology Bulk/Deep Wet Etch Actuation Mechanism Pressure (External) Signal Condition Two chips/Single chip



Pad	Symbol	Description
1	V _{out} +	Output voltage
2	V _{in} +	Supply voltage
3	V _{out} -	Output voltage
4	V _{in} -	Supply voltage
5	V _{in} -	Supply voltage
6	V _{in} -	Supply voltage
GND	GND	Ground

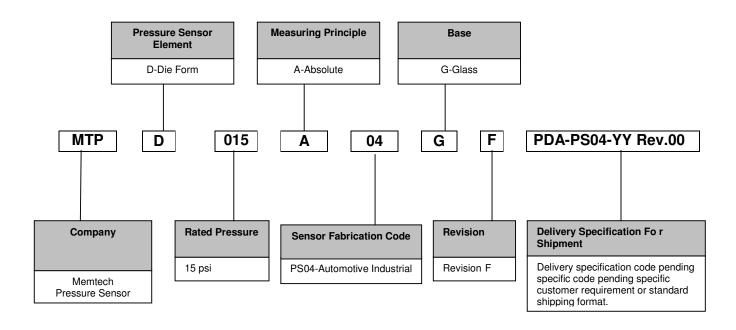
MEMSENZ[™] III Transduction Principle Resistive Processing Technology Surface Actuation Mechanism Thermal Signal Condition Two chips MEMSENZ[™] IV Transduction Principle Capacitive Processing Technology Bulk Actuation Mechanism Sound Signal Condition Two chips

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MTPD-015A-04G-F

Uncompensated Pressure Sensor Die

HOW TO SPECIFY PART NUMBER



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MEMSENZ[™] II Transduction Principle Piezoresistive Processing Technology Bulk/Deep Wet Etch Actuation Mechanism Pressure (External) ignal Condition Two chips/Single chip

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